DE LA RECHERCHE À L'INDUSTRIE





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THIN METALLIC LINERS FOR HOHLRAUM





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I. CONTEXT

- **II. LINERS FABRICATION**
- III. RESULTS
- **IV. CONCLUSION**



<u>CONTEXT</u>: Change hohlraum albedo (completely or locally)



STUDY OF NEW KIND OF HOHLRAUM



FABRICATION SYNOPTIC

FULL LINER



LOCALIZED LINER



ELECTRON BEAM EVAPORATION OR MAGNETRON SPUTTERING

Evaporation configuration



Evaporation is well adapted for material with low vapor pressure (e.g. **copper**)

Evaporation chamber







Examples of aluminum and brass mandrels

Sputtering configuration



Sputtering is useful for material with high vapor pressure (e.g. **titanium**)

THIN METALLIC COATING FROM 1 µm TO 3 µm ON METALLIC MANDREL



□ COPPER LINER IN GOLD HOHLRAUM





FEASIBILITY OF COPPER FULL LINER IN GOLD HOHLRAUM IS DEMONSTRATED 6

COPPER FULL LINER RESULTS



Observations:

- few porosities are observables in zone 1 and 3 (shadow effect)
- microstructure is well dense in zone 2
- > thickness is well uniform: 1.7 μ m ± 0.2 μ m (12%)



FEASIBILITY OF COPPER FULL LINER IN GOLD HOHLRAUM IS DEMONSTRATED 7



Ti cross section (FIB-SEM)

Ti coating is well dense and thickness is uniform along the hohlraum

FEASIBILITY OF TITANIUM FULL LINER IN PLASTIC HOHLRAUM IS DEMONSTRATED



FABRICATION SYNOPTIC

Characterization





Excimer ArF laser (193 nm, 350mJ/pulse, rate 50 Hz)

4 motorized axis (X,Y, Z, Θ)



2 rings (width~400µm/360°)





4 spots (\emptyset 800µm) on the equator



SELECTED ABLATION OF SACRIFICIAL POLYMER LAYER

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LOCALIZED LINER RESULTS

CONTROL OF STEP HIGHER BY OPTICAL INTERFEROMETRY



(polymer is lightly colored)

COPPER RINGS ARE COMPLETE (w=400µm and t=1.6µm)

CHARACTERIZATION OF LOCALIZED LINER IS NOT A PROBLEM



LOCALIZED LINER RESULTS

Cu rings on Al mandrel



(w=130µm/360°)

Gold plating (30 µm) and aluminum chemical attack



Localized rings of Cu in Au hohlraum « copper rings still present but partially dissolved »

Ti rings on brass mandrel



CHON thermosetting resin and mandrel chemical attack



(w=400µm/360°) Localized rings of Ti in CHON hohlraum « *Ti rings are well transferred but a weak adherence is observed at Ti/CHON interface*»



FEASIBILITY OF <u>FULL</u> LINER IS DEMONSTRATED:

- **Cu 1.7 μm thick in Au hohlraum:** *yield* 30%
- > Ti 2.5 µm thick in CHON hohlraum: yield 100%

FEASIBILITY OF LOCALIZED LINER HAVE TO BE CONSOLIDATED:

- > Cu in Au hohlraum: partially dissolved
- > Ti in CHON hohlraum: partially peeled-off

PERSPECTIVES:

- Increase yield in case of copper: [HCI], T°, mandrel nature, …
- Improve adhesion at Ti/CHON interface: stress, ion gun treatment, primer coating, …
- > Development of a non-destructive method to control liner: X-ray tomography, ...
- > Aging and environment stability studies

Thank you !



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